

In the specification:

Please replace paragraph [0004] with the following amended paragraph:

[0004] There are many situations in which it is desirable to have the ability to measure or monitor one or more parameters or make visual inspections within a harsh or hostile environment. For example, it is desirable to have the ability to monitor one or more parameters, such as temperature and pressure, within the environment of a semiconductor wafer processing chamber. The environment within such a semiconductor wafer processing chamber, particularly during the processing of semiconductor wafers, includes high vacuum pressures. The use of existing, standard, unprotected monitoring equipment and/or techniques within such a semiconductor wafer processing chamber or any other such harsh or hostile environment is ineffective because most existing monitoring equipment is simply not constructed to withstand the severe[,,] pressures encountered within such a semiconductor wafer processing chamber and/or the serve severe temperatures, pressures and other environmental factors present in other such harsh or hostile environments. The present invention overcomes the problems of the prior art by providing a flexible, generally tubular elongated protective housing made of a non-porous, hermetically sealed, corrosive resistant material for containing the sensitive measuring and/or monitoring equipment employed for measuring or monitoring one or more parameters within a semiconductor wafer processing chamber or other such harsh or hostile environment. The present invention is particularly useful in calibration, inspection and maintenance within a semiconductor wafer processing chamber.